

| | Hits | Search Text | DBs |
|---|------|---|--|
| 6 | 3 | 355/67.ccls. and ((illuminat\$4 or expos\$4 or irradiat\$4) same ((beam near9 split\$4) or mirror) same (pluralit\$4 or multiple or two or three)) and ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near (mask or pixel))) same pattern\$4 same array) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 7 | 2 | 355/77.ccls. and ((illuminat\$4 or expos\$4 or irradiat\$4) same ((beam near9 split\$4) or mirror) same (pluralit\$4 or multiple or two or three)) and ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near (mask or pixel))) same pattern\$4 same array) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

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| 8 | 0 | 430/5.ccls. and ((illuminat\$4 or expos\$4 or irradiat\$4) same ((beam near9 split\$4) or mirror) same (pluralit\$4 or multiple or two or three)) and ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near (mask or pixel))) same pattern\$4 same array) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 9 | 0 | ((illuminat\$4 or expos\$4 or irradiat\$4) same ((beam near9 split\$4) or mirror) same (pluralit\$4 or multiple or two or three)) and ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near (mask or pixel))) same pattern\$4 same array) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

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| 10 | 0 | ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near (mask or pixel))) same pattern\$4 same array) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 11 | 0 | ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near16 (mask or pixel))) same pattern\$4 same array) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 12 | 1 | ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same (multiple or pluralit\$9) same (pupil near9 plane) same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |

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| 13 | 23 | ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) | US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB |
| 14 | 0 | ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and ((SLM or (pattern\$9 near16 array) or (pattern\$4 near18 plural\$5) or (position\$4 near12 arrang\$5)) same (expos\$4 or irradiat\$4 or illuminat\$4 or beam\$3) same angle same ((NA or (numerical near9 aperture)) near16 (high\$5 or larg\$3 or big\$4))) | US-PGPUB |

| | Hits | Search Text | DBs |
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| 15 | 0 | ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and ((SLM or (pattern\$9 near16 array) or (pattern\$4 near18 plural\$5 near22 array) or (position\$4 near12 arrang\$5)) same (expos\$4 or irradiat\$4 or illuminat\$4 or beam\$3) same angle same ((NA or (numerical near9 aperture)) near16 (high\$5 or larg\$3 or big\$4))) | US-PGPUB |